



**AFRL-RZ-WP-TP-2012-0141**

**ON THE THROUGH-THICKNESS CRITICAL CURRENT  
DENSITY OF AN  $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$  FILM CONTAINING A  
HIGH DENSITY OF INSULATING, VORTEX-PINNING  
NANOPRECIPITATES (POSTPRINT)**

**S.I. Kim, F. Kametani, Z. Chen, A. Gurevich, and D.C. Larbalestier**

**Florida State University**

**T. Haugan and P. Barnes**

**Mechanical Energy Conversion Branch  
Energy/Power/Thermal Division**

**FEBRUARY 2012**

**Approved for public release; distribution unlimited.**

*See additional restrictions described on inside pages*

**STINFO COPY**

**© 2007 American Institute of Physics**

**AIR FORCE RESEARCH LABORATORY  
PROPULSION DIRECTORATE  
WRIGHT-PATTERSON AIR FORCE BASE, OH 45433-7251  
AIR FORCE MATERIEL COMMAND  
UNITED STATES AIR FORCE**

REPORT DOCUMENTATION PAGE				Form Approved OMB No. 0704-0188	
<p>The public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing the collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestions for reducing this burden, to Department of Defense, Washington Headquarters Services, Directorate for Information Operations and Reports (0704-0188), 1215 Jefferson Davis Highway, Suite 1204, Arlington, VA 22202-4302. Respondents should be aware that notwithstanding any other provision of law, no person shall be subject to any penalty for failing to comply with a collection of information if it does not display a currently valid OMB control number. <b>PLEASE DO NOT RETURN YOUR FORM TO THE ABOVE ADDRESS.</b></p>					
1. REPORT DATE (DD-MM-YY) February 2012		2. REPORT TYPE Journal Article Postprint		3. DATES COVERED (From - To) 04 April 2005 – 04 April 2007	
4. TITLE AND SUBTITLE ON THE THROUGH-THICKNESS CRITICAL CURRENT DENSITY OF AN $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$ FILM CONTAINING A HIGH DENSITY OF INSULATING, VORTEX-PINNING NANOPRECIPITATES (POSTPRINT)				5a. CONTRACT NUMBER In-house	
				5b. GRANT NUMBER	
				5c. PROGRAM ELEMENT NUMBER 62203F	
6. AUTHOR(S) S.I. Kim, F. Kametani, Z. Chen, A. Gurevich, and D.C. Larbalestier (Florida State University) T. Haugan and P. Barnes (AFRL/RZPG)				5d. PROJECT NUMBER 3145	
				5e. TASK NUMBER 32	
				5f. WORK UNIT NUMBER 314532ZE	
7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES) Florida State University Applied Superconductivity Center National High Magnetic Field Laboratory Tallahassee, FL 32310				Mechanical Energy Conversion Branch (AFRL/RZPG) Energy/Power/Thermal Division Air Force Research Laboratory, Propulsion Directorate Wright-Patterson Air Force Base, OH 45433-7251 Air Force Materiel Command, United States Air Force	
9. SPONSORING/MONITORING AGENCY NAME(S) AND ADDRESS(ES) Air Force Research Laboratory Propulsion Directorate Wright-Patterson Air Force Base, OH 45433-7251 Air Force Materiel Command United States Air Force				10. SPONSORING/MONITORING AGENCY ACRONYM(S) AFRL/RZPG	
				11. SPONSORING/MONITORING AGENCY REPORT NUMBER(S) AFRL-RZ-WP-TP-2012-0141	
12. DISTRIBUTION/AVAILABILITY STATEMENT Approved for public release; distribution unlimited.					
13. SUPPLEMENTARY NOTES Journal article published <i>Applied Physics Letters</i> , Vol. 90, 2007. © 2007 American Institute of Physics. The U.S. Government is joint author of this work and has the right to use, modify, reproduce, release, perform, display, or disclose the work. PA Case Number: AFRL/WS-07-0798; Clearance Date: 04 Apr 2007. Work on this effort was completed in 2007.					
14. ABSTRACT Using sequential ion milling the authors have studied the thickness dependence of the critical current density $J_c(H)$ of a single crystal $1\mu\text{m}$ thick $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$ thin film containing 5 vol % of insulating $\text{Y}_2\text{BaCuO}_5$ (Y211) nanoparticles in order to better understand how to obtain high critical currents in thick films. Except very near the interface where the defect density was enhanced, $J_c(H)$ in the body of the film was uniform and independent of thickness with a high maximum pinning force of $8.8\text{ GN/m}^3$ at 77 K. The authors conclude that the nanoscale Y211 precipitates result in strong, three-dimensional pinning characterized by a pin spacing of $\sim 30\text{ nm}$ , much smaller than the film thickness.					
15. SUBJECT TERMS ion, film, currents, nanoscale, precipitates, pinning, density, thickness, independent, insulating, pin, uniform					
16. SECURITY CLASSIFICATION OF:			17. LIMITATION OF ABSTRACT: SAR	18. NUMBER OF PAGES 10	19a. NAME OF RESPONSIBLE PERSON (Monitor) Timothy J. Haugan 19b. TELEPHONE NUMBER (Include Area Code) N/A
a. REPORT Unclassified	b. ABSTRACT Unclassified	c. THIS PAGE Unclassified			

# On the through-thickness critical current density of an $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$ film containing a high density of insulating, vortex-pinning nanoprecipitates

S. I. Kim,<sup>a)</sup> F. Kametani, Z. Chen, A. Gurevich, and D. C. Larbalestier  
*Applied Superconductivity Center, National High Magnetic Field Laboratory, Florida State University,  
Tallahassee, Florida 32310*

T. Haugan and P. Barnes  
*Air Force Research Laboratory, Dayton, Ohio 45433*

(Received 14 March 2007; accepted 24 May 2007; published online 18 June 2007)

Using sequential ion milling the authors have studied the thickness dependence of the critical current density  $J_c(H)$  of a single crystal 1  $\mu\text{m}$  thick  $\text{YBa}_2\text{Cu}_3\text{O}_{7-x}$  thin film containing  $\sim 5$  vol % of insulating  $\text{Y}_2\text{BaCuO}_5$  (Y211) nanoparticles in order to better understand how to obtain high critical currents in thick films. Except very near the interface where the defect density was enhanced,  $J_c(H)$  in the body of the film was uniform and independent of thickness with a high maximum pinning force of 8.8 GN/m<sup>3</sup> at 77 K. The authors conclude that the nanoscale Y211 precipitates result in strong, three-dimensional pinning characterized by a pin spacing of  $\sim 30$  nm, much smaller than the film thickness. © 2007 American Institute of Physics. [DOI: 10.1063/1.2749437]

$\text{YBa}_2\text{Cu}_3\text{O}_{7-\delta}$  (YBCO) is a very versatile superconductor into which many types of vortex-pinning centers can be introduced.<sup>1-6</sup> As the limits to the current-carrying capability of this technological compound are explored, the commonly observed decline of  $J_c$  with increasing film thickness  $t$  (Refs. 7–12) is still not well understood. Such a thickness dependence may result from the transition from the two-dimensional pinning of rigid vortex lines in thinner films to the three-dimensional (3D) pinning of deformable vortices even for a completely uniform pinning nanostructure.<sup>13,14</sup> However, there are also many reports of microstructures varying across YBCO films, which can also cause a thickness-dependent  $J_c(t)$ . For example, Foltyn *et al.*,<sup>15</sup> who studied single crystal YBCO films grown by pulsed laser deposition (PLD) without any added second phase, found that the thickness dependence of the average  $J_c$  can result from a decrease of the local  $J_c$  out to a  $t$  of  $\sim 0.65$   $\mu\text{m}$ , followed by a thickness-independent  $J_c$ . They ascribed the high  $J_c$  at the interface at the  $\text{CeO}_2$  cap layer to a 20 nm thick caging array of interface dislocations which strongly enhance local vortex pinning.

We recently investigated the thickness dependence of  $J_c$  in YBCO coated conductors made by the metal organic deposition (MOD) process and found no evidence for dimensional pinning crossover as the reason for the observed decline of  $J_c$  with increasing  $t$ .<sup>16</sup> Analysis of the thickness dependence of  $J_c(H)$ , the normal state resistivity, and the microstructure showed that MOD films exhibit microstructural degradation which grows as the films thicken, producing a thickness-dependent reduction of the effective current-carrying cross section  $A_{\text{eff}}$ . High angle grain boundaries,<sup>17-21</sup> porosity,<sup>12,16</sup> insulating phases,<sup>22</sup> or other macroscopic planar obstacles<sup>23</sup> reduce the cross section for current flow. In fact, the MOD films exhibited both strong single vortex pinning and a thickness-dependent porosity, which together result in the quasilinear decay of the average  $J_c$  with increasing  $t$ .

To better test the physical mechanisms at play, we have studied the thickness dependence of  $J_c$  in a PLD YBCO film to which insulating  $\text{Y}_2\text{BaCuO}_5$  (Y211) particles were delib-

erately added. Our hypothesis was that the addition of insulating nanoparticles should yield a thickness-independent  $J_c$ , since strong pins should enable each vortex segment to be pinned independently. In this letter, we show that such precipitates do take YBCO into the very desirable strong 3D pinning regime, in which the longitudinal pinning correlation length is much shorter than the film thickness, and the local  $J_c$  is then independent of  $t$ . In principle, this permits a high and a thickness-independent  $J_c$  in thick films, provided that thickness degradation of the current-carrying cross section and variation of the second-phase vortex-pinning structure are avoided.

An YBCO film was deposited by PLD on a single crystal  $\text{SrTiO}_3$  substrate. The Y211 nanoparticles were introduced by alternate deposition of Y211 ( $\sim 0.8$  nm) and YBCO ( $\sim 16.5$  nm).<sup>1</sup> A 50  $\mu\text{m}$  wide  $\times 400$   $\mu\text{m}$  long bridge was patterned and was then sequentially thinned with 500 eV Ar ions impinging at 45° while the sample was cooled to  $\sim 230$  K. After each milling step,  $J_c(H)$  was measured (1  $\mu\text{V}/\text{cm}$  criterion) at 77 K for magnetic fields up to 10 T applied perpendicular to the film surface. The full thickness of the YBCO was 1.0  $\mu\text{m}$ , and the thickness of each thinned sample was measured with a Tencor profilometer. Cross-section transmission electron microscopy (TEM) imaging was performed in a Philips CM200UT.

This sample exhibited a full-thickness  $J_c(0 \text{ T}, 77 \text{ K})$  of 3.4 MA/cm<sup>2</sup>,  $T_c$  of 90.0 K defined at the onset of resistance, and an irreversibility field  $H_{\text{ir}}(77 \text{ K})$  of 8.8 T measured at  $J_c = 100 \text{ A}/\text{cm}^2$ . The maximum pinning force  $F_{p,\text{max}}$  was  $\sim 8.8 \text{ GN}/\text{m}^3$ .

Figure 1 shows the  $J_c(t)$  data as a function of the residual thickness for each milling step. The critical current per unit width  $I_c^*$  shown in the inset of Fig. 1 exhibits a linear dependence on  $t$ , which extrapolates to a nonzero value of  $I_c^*$  at zero  $t$ . Such a linear dependence is inconsistent with the collective pinning scenario. Instead, the  $I_c^*(t)$  data unambiguously indicate a uniform local  $J_c$  in the bulk of the film, and a thin, higher  $J_c$  layer near the substrate. From the constant slope of  $I_c^*(t)$ , we calculated the local  $J_c \sim 3.1 \text{ MA}/\text{cm}^2$  in the bulk of the film. The global  $J_c(t) = J_{c0}(1 + t_0/t)$  thus increases as  $t$  decreases because of the very high

<sup>a)</sup>Electronic mail: sikim@asc.magnet.fsu.edu

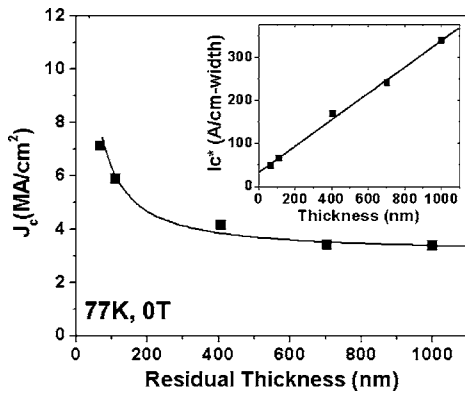


FIG. 1. Self-field 77 K  $J_c(t)$  data as a function of the residual thickness after ion milling. The solid line represents  $J_{c0}(t) = J_c(1) + t_0(t)$ . The inset shows the critical current per unit width  $I_c^*(0 \text{ T}, 77 \text{ K})$ , which exhibits a linear dependence on  $t$  with a nonzero intercept at zero  $t$ .

$J_c(7.1 \text{ MA/cm}^2)$  of the 60–70 nm thick interface layer. The pinning structure in this highly defected interface layer will be addressed below.

The  $J_c(H)$  at 77 K for different thicknesses are shown in Fig. 2(a). The overall shape of the  $J_c(H)$  curves is rather insensitive to  $t$ , although the magnitude does increase at small  $t$  due to the high  $J_c$  interface layer. For comparison,  $J_c(H)$  curves for a 280 nm YBCO film grown by PLD on a single crystal  $(\text{La}_{0.30}\text{Sr}_{0.70})(\text{Al}_{0.65}\text{Ta}_{0.35})\text{O}_3$  (LSAT) substrate<sup>24</sup> and for 1  $\mu\text{m}$  YBCO film grown by MOD on a single crystal yttrium-stabilized zirconia<sup>21</sup> (YSZ) are also

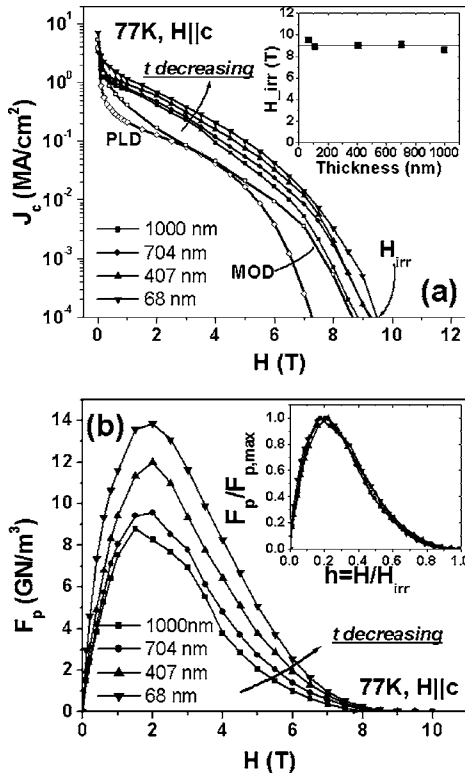


FIG. 2. (a)  $J_c(H)$  at 77 K for different thicknesses.  $J_c(H)$  curves for a 280 nm YBCO film grown by PLD on a single crystal LSAT substrate (Ref. 24) and for a 1  $\mu\text{m}$  YBCO film made by MOD on a single YSZ crystal (Refs. 16 and 21) are shown for comparison. The inset shows the irreversibility field  $H_{irr}$ , determined at  $J_c = 100 \text{ MA/cm}^2$ , as a function of  $t$ . (b) Bulk pinning force plot  $F_p(H)$  for different thicknesses. The inset shows that the normalized pinning force curves  $F_p(H)/F_{p,max} = f(H/H_{irr})$  do not change as thickness changes.

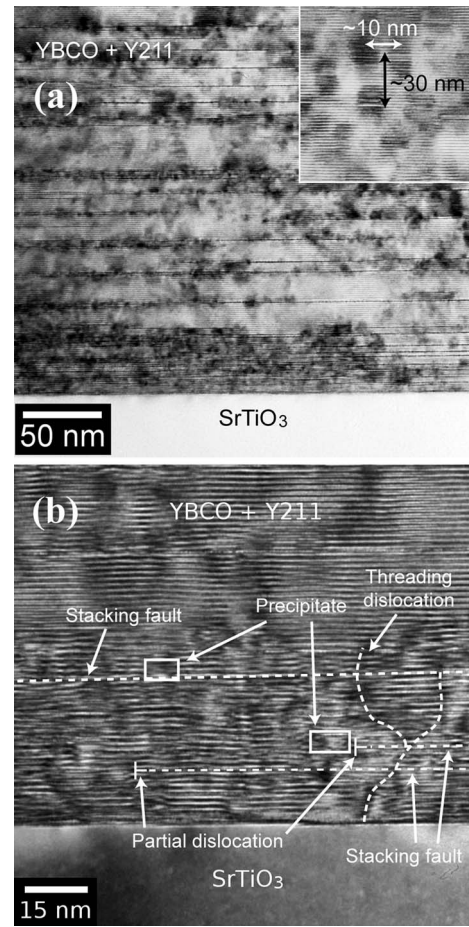


FIG. 3. (a) Cross-sectional TEM image shows a high density of randomly distributed Y211 nanoprecipitates. (b) Close-up view near the interface layer. Additional defects are present near the interface, especially higher density of stacking faults. (Some stacking faults, Y211 precipitates, and threading dislocations are labeled.) The YBCO matrix is highly distorted because of tangled stacking faults with Y211 precipitates and threading dislocations, producing high strain fields and lattice buckling.

shown. Neither the PLD nor MOD film had deliberately added second-phase particles, although the MOD films do have a complex pinning microstructure that contains pores, stacking faults, and  $\text{Y}_2\text{O}_3$  particles. The strong vortex pinning of the present sample is quite evident. It results in much higher  $J_c$  values at all fields above a few tenths of a tesla, although the self-field  $J_c$  values of all three samples vary only from 3.4 to 5.3 A/cm<sup>2</sup>. The  $H_{irr}$  are essentially independent of  $t$  [inset of Fig. 2(a)], similar to what we found for the MOD film with strong pinning<sup>16</sup> but quite different from the decreasing  $H_{irr}(t)$  in the PLD film on LSAT.<sup>24</sup> The thickness-dependent bulk flux pinning force curves  $F_p(H) = \mu_0 H \times J_c(H)$  are shown in Fig. 2(b). The magnitude of the  $F_{p,max}$  increases as  $t$  decreases because of the contribution of the strong-pinning interface layer. However, even at full thickness,  $F_{p,max} = 8.8 \text{ GN/m}^3$  is more than two times higher than  $F_{p,max} = 4.1 \text{ GN/m}^3$  for a 1  $\mu\text{m}$  MOD film,<sup>16,21</sup> while at the thinnest layer measured,  $F_{p,max}$  of our samples reaches  $13.8 \text{ GN/m}^3$ . However, the inset of Fig. 2(b) clearly shows that the normalized pinning forces  $F_p/F_{p,max}$  plotted against the reduced fields  $H/H_{irr}$  are essentially independent of  $t$ , consistent with our conclusion that the pinning mechanisms are independent of  $t$ .

Figure 3 shows cross-sectional TEM images, which reveal a high density of Y211 precipitates (spheres with dark



contrast) and stacking faults (horizontal black lines). Typical sizes of the Y211 precipitates are  $\sim 4\text{--}8$  nm [inset of Fig. 3(a)]; however, the effective pinning size including strain field is  $\sim 10$  nm. As a result, the nominal volume fraction of the precipitates of  $\sim 5$  vol % effectively increases to  $\sim 10$  vol % if the strained regions are included. Within each thickness slice, the Y211 precipitates are rather randomly distributed in the YBCO, the average spacing being  $\sim 30$  nm along the  $c$  axis and  $\sim 10$  nm in the  $ab$  plane. [inset of Fig. 3(a)]. However, separation between the nanoprecipitates along the  $c$  axis may be smaller within the 60 nm interface layer where the stacking fault density is much larger than in the body of the film. It is shown in Fig. 3(a) that the Y211 tend to cluster and tangled with the stacking faults. Figure 3(b) also indicates that there are several threading dislocations, which are cut into short segments by the stacking faults, making a dense defect network near the interface, a structure which is consistent with the much stronger pinning near the interface.

Our experiment was motivated by the idea that the Y211 nanoprecipitates would provide strong 3D pinning so that vortices are chopped into separate, individually pinned segments.<sup>16</sup> This condition is indeed fulfilled as indicated by the linear  $I_c^*(t)$  behavior which implies a thickness-independent local  $J_c$  in the bulk of the film, and by the very high  $F_{p,\max}$  of  $\sim 8.8$  GN/m<sup>3</sup> evaluated over the whole film thickness.

To check if these  $J_c$  values are consistent with the observed precipitate density, we estimated the maximum  $J_c$  which would be determined by depinning of elliptical vortex segments whose ends are fixed by neighboring nanoprecipitates with mean spacing  $d$ . The  $J_c$  can then be estimated from<sup>25</sup>

$$J_c = \frac{\phi_0}{2\pi\mu_0\lambda_a\lambda_c d} \ln \frac{d}{\xi_c}. \quad (1)$$

Here,  $\phi_0$  is the flux quantum,  $\mu_0$  is the magnetic permeability,  $\lambda_a$  and  $\lambda_c$  are the London penetration depths in the  $ab$  plane and along the  $c$  axis, respectively, and  $\xi_c$  is the coherence length along the  $c$  axis. If we take  $\lambda_a = 0.4$   $\mu\text{m}$ ,  $\lambda_c = 2$   $\mu\text{m}$ , and  $\xi_c = 1$  nm at 77 K with the observed average mean Y211 separation  $d$  of  $\sim 30$  nm, Eq. (1) gives  $J_c \sim 3.7$  MA/cm<sup>2</sup>, in agreement with the observed local  $J_c$  of  $\sim 3.1$  MA/cm<sup>2</sup> away from the interface. The interface layer exhibits even stronger pinning where we expect an enhanced Y211 precipitate density. According to Eq. (1), the measured self-field  $J_c$  value of 7.1 MA/cm<sup>2</sup> at the interface layer implies a mean pin separation of  $\sim 10$  nm, consistent with the smaller pin separation. Moreover, as shown in Fig. 3(b), the stacking faults have correlated partial dislocations tangled with the Y211 precipitates and the threading dislocations, producing strong strain fields, which may enhance the pinning further. This strong-pinning behavior with very high  $F_{p,\max}$  of 13.8 GN/m<sup>3</sup> reaches about two-thirds of the present champion samples made with the artificial pinning center distributions.<sup>5,6,26</sup>

The production of uniform, dense arrays of nanoprecipitates is a natural route to a uniform through-thickness, vortex-pinning microstructure with very high and thickness-independent  $J_c$ . The significant potential of nanoscale pin-

ning engineering is well illustrated both by the results of this work and by the previous spectacularly high  $J_c$  values for the artificial pinning center structures.<sup>5,26</sup> In the present case,  $\sim 5$  vol % of insulating Y211 particles of  $\sim 4\text{--}8$  nm, with separations of 10–30 nm, produce strong 3D pinning indeed.

This work was supported by the AFOSR-supported MURI “Critical Scientific Challenges of Coated Conductors” Contract No. F49620-01-1-0464.

- <sup>1</sup>T. Haugan, P. N. Barnes, R. Wheeler, F. Meisenkothen, and M. Sumption, *Nature* (London) **430**, 867 (2004).
- <sup>2</sup>J. L. Macmanus-Driscoll, S. R. Foltyn, Q. X. Jia, H. Wang, A. Serquis, L. Civale, B. Maiorov, M. E. Hawley, M. P. Maley, and D. E. Peterson, *Nat. Mater.* **3**, 439 (2004).
- <sup>3</sup>X. Y. Song, Z. J. Chen, S. I. Kim, D. M. Feldmann, D. Larbalestier, J. Reeves, Y. Y. Xie, and V. Selvamanickam, *Appl. Phys. Lett.* **88**, 212508 (2006).
- <sup>4</sup>N. Long, N. Strickland, B. Chapman, N. Ross, J. Xia, X. Li, W. Zhang, T. Kodanandath, Y. Huang, and M. Rupich, *Supercond. Sci. Technol.* **18**, S405 (2005).
- <sup>5</sup>M. Miura, Y. Yoshida, Y. Ichino, Y. Takai, K. Matsumoto, A. Ichinose, S. Horii, and M. Mukaida, *Jpn. J. Appl. Phys., Part 2* **45**, L11 (2006).
- <sup>6</sup>J. Gutierrez, A. Llordes, J. Gazquez, M. Gibert, N. Roma, A. Pomar, F. Sandiumenge, N. Mestres, T. Puig, and X. Obradors, *Nat. Mater.* **6**, 367 (2007).
- <sup>7</sup>S. R. Foltyn, P. N. Arendt, Q. X. Jia, H. Wang, J. L. MacManus-Driscoll, S. Kreiskott, R. F. DePaula, L. Stan, J. R. Groves, and P. C. Dowden, *Appl. Phys. Lett.* **82**, 4519 (2003).
- <sup>8</sup>S. R. Foltyn, Q. X. Jia, P. N. Arendt, L. Kinder, Y. Fan, and J. F. Smith, *Appl. Phys. Lett.* **75**, 3692 (1999).
- <sup>9</sup>S. R. Foltyn, P. Tiwari, R. C. Dye, M. Q. Le, and X. D. Wu, *Appl. Phys. Lett.* **63**, 1848 (1993).
- <sup>10</sup>R. Feenstra, A. A. Gapud, F. A. List, E. D. Specht, D. K. Christen, T. G. Holesinger, and D. A. Feldmann, *IEEE Trans. Appl. Supercond.* **15**, 2803 (2005).
- <sup>11</sup>B. W. Kang, A. Goyal, D. R. Lee, J. E. Mathis, E. D. Specht, P. M. Martin, D. M. Kroeger, M. Paranthaman, and S. Sathyamurthy, *J. Mater. Res.* **17**, 1750 (2002).
- <sup>12</sup>R. L. S. Emurgo, J. Z. Wu, T. Aytug, and D. K. Christen, *Appl. Phys. Lett.* **85**, 618 (2004).
- <sup>13</sup>P. H. Kes and C. C. Tsuei, *Phys. Rev. B* **28**, 5126 (1983).
- <sup>14</sup>A. Gurevich, *Superconductivity for Electric Systems 204 Annual Peer Review* (unpublished) ([http://www.energetics.com/meetings/supercon04/pdfs/presentations/f\\_uw\\_coated\\_conductor\\_peer\\_rev\\_04final.pdf](http://www.energetics.com/meetings/supercon04/pdfs/presentations/f_uw_coated_conductor_peer_rev_04final.pdf)).
- <sup>15</sup>S. R. Foltyn, H. Wang, L. Civale, Q. X. Jia, P. N. Arendt, B. Maiorov, Y. Li, M. P. Maley, and J. L. MacManus-Driscoll, *Appl. Phys. Lett.* **87**, 064521 (2005).
- <sup>16</sup>S. I. Kim, A. Gurevich, X. Song, X. Li, W. Zhang, T. Kodanandath, M. W. Rupich, T. G. Holesinger, and D. C. Larbalestier, *Supercond. Sci. Technol.* **19**, 968 (2006).
- <sup>17</sup>D. Dimos, P. Chaudhari, and J. Mannhart, *Phys. Rev. B* **41**, 4038 (1990).
- <sup>18</sup>D. T. Verebelyi, D. K. Christen, R. Feenstra, C. Cantoni, A. Goyal, D. F. Lee, M. Paranthaman, P. N. Arendt, R. F. DePaula, J. R. Groves, and C. Prouteau, *Appl. Phys. Lett.* **76**, 1755 (2000).
- <sup>19</sup>D. M. Feldmann, D. C. Larbalestier, D. T. Verebelyi, W. Zhang, Q. Li, G. N. Riley, R. Feenstra, A. Goyal, D. F. Lee, M. Paranthaman, D. M. Kroeger, and D. K. Christen, *Appl. Phys. Lett.* **79**, 3998 (2001).
- <sup>20</sup>N. F. Heinig, R. D. Redwing, J. E. Nordman, and D. C. Larbalestier, *Phys. Rev. B* **60**, 1409 (1999).
- <sup>21</sup>S. I. Kim, D. M. Feldmann, D. T. Verebelyi, C. Thieme, X. Li, A. A. Polyanskii, and D. C. Larbalestier, *Phys. Rev. B* **71**, 104501 (2005).
- <sup>22</sup>Z. Chen, D. M. Feldmann, X. Song, S. I. Kim, A. Gurevich, J. Reeves, Y. Y. Xie, V. Selvamanickam, and D. C. Larbalestier, *Supercond. Sci. Technol.* (to be published).
- <sup>23</sup>M. Friesen and A. Gurevich, *Phys. Rev. B* **63**, 064521 (2001).
- <sup>24</sup>S. I. Kim, Z. Chen, A. Gurevich, F. Kametani, K.-J. Choi, C.-B. Eom, and D. C. Larbalestier (unpublished).
- <sup>25</sup>E. H. Brandt, *Phys. Rev. Lett.* **69**, 1105 (1992).
- <sup>26</sup>K. Matsumoto, T. Horide, A. Ichinose, S. Horii, Y. Yoshida, and M. Mukaida, *Jpn. J. Appl. Phys., Part 2* **44**, L246 (2005).